Effect of heat treating metallic constituents on the properties of Cu$_2$ZnSnSe$_4$ thin films formed by a two-stage process


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**A B S T R A C T**

In this study Cu$_2$ZnSnSe$_4$ (CZTSe) thin films were grown by a two-stage process that involved sputter deposition of a Cu/ Sn/Zn/Cu metallic stack, annealing the stack at various temperatures for 30 min, evaporation of a Se cap over the metallic stack thus forming a precursor layer, and subjecting the precursor layer to a final high temperature reaction step at 550 °C. Different samples were prepared with annealing temperatures of the metallic stacks ranging from 200 °C to 350 °C. The results showed that heat treatment of the metallic stacks did not cause much change in their morphology and elemental composition, however their phase content changed noticeably when the anneal temperature was raised to 250 °C. Specifically, while the metallic films were dominated by CuSn and Cu$_2$Zn$_2$ phases at low temperatures, the dominant phase shifted to Cu$_2$Sn$_2$ at the annealing temperature of 250 °C and higher. Also formation of a distinct Cu$_2$Zn$_2$ phase was observed upon annealing at temperatures at or above 250 °C. After reaction with Se, the CZTSe layer obtained from the metallic film, which was annealed at 250 °C was found to be the best in terms of its composition, crystalline quality and purity, although it contained a small amount of CuSe. The other layers were found to contain small amounts of secondary phases such as SnSe, Cu$_2$Se$_2$, ZnSe and Cu$_2$SnSe$_3$. SEM micrographs showed denser structure for CZTSe layers grown from metallic films annealed at or above 250 °C. Optical band gap, resistivity and carrier concentration of the best quality CZTSe film were found to be about 0.87 eV, 2 Ω-cm and 4 × 10$^{17}$ cm$^{-3}$, respectively.

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1. Introduction

Thin film solar cells based on Cu (In, Ga) Se$_2$ (CIGS) have shown significant improvement and attracted much attention due to their application in the photovoltaics industry. Although CIGS-based devices are to date the most efficient thin film solar cells with a champion conversion efficiency of 22.3% [1], limited supplies of In and Ga are expected to restrict manufacturing volume of this technology. One of the alternative compounds to replace CIGS in a solar cell structure is Cu$_2$ZnSn(S,Se)$_4$ (CZTSe) where In and Ga are substituted by tin (Sn) and zinc (Zn). CZTSe has drawn significant attention from the research community due to its composition comprising earth-abundant materials [2], its suitable direct band gap energy in the range of ~0.9 eV to 1.6 eV [3,4], and due to its high optical absorption coefficient ($\geq 10^4$ cm$^{-1}$). Although the theoretical efficiency of a CZTSe-based thin film solar cell is estimated to be over 30% [5], so far researchers could only demonstrate 10.4% conversion efficiency for Cu$_2$ZnSnSe$_4$ devices [6], and 12.6% for Cu$_2$ZnSn(S,Se)$_4$ based cells [7]. The reasons for this shortcoming are still being investigated.

Fabrication methods for CZTSe absorbers involve both vacuum and non-vacuum techniques. Vacuum methods include thermal evaporation [8], e-beam evaporation [9], pulsed laser deposition [10], and sputtering [11]. The non-vacuum methods include electrochemical deposition [12], spray pyrolysis [13], and sol-gel deposition [14]. Recently published work on CZTSe thin films include topics such as optimization of film growth parameters (e.g. annealing temperature/time [15]), investigation of composition effects on the film properties [16], and study of possible influence of using differently prepared stacked metallic precursor layers on the properties of the compound films grown by two-stage processes [17].

Gurav et al., in their 2013 study, showed that a soft-annealing treatment of Cu-Zn-Sn containing metallic layers produced by an electroplating method had significant influence on the properties of Cu$_2$ZnSnSe$_3$ (CZTS) layers obtained from such layers after a high temperature sulfurization step [18]. In that study the metallic films were subjected to a soft-annealing process for 1 h at a temperature range of 250–350 °C and then sulfurized at 580 °C for 2 h. It was concluded...
that the best soft-annealing temperature was 300 °C and such a treatment improved the properties of the resulting films. There has not been such a study yet investigating possible effects of soft-annealing on the properties of CZTSe layers grown by a two-stage technique. In this contribution we present data on the influence of relatively mild soft-annealing steps on the properties of CZTSe films obtained by reacting sputter deposited and annealed metallic stacks with Se.

2. Experimental

Kesterite CZTSe thin films were obtained by a two-stage process that involved high temperature annealing of precursor layers containing Cu, Zn, Sn and Se. Preparation of the precursor layers included the steps of: i) depositing Cu, Zn, and Sn onto unheated molybdenum (Mo) coated soda lime glass (SLG) substrates by DC magnetron sputtering from high-purity Cu (5 N), Sn (4 N), and Zn (4 N) targets in one pump-down to form metallic stacks, ii) heat treating the metallic stacks at various annealing temperatures, and iii) evaporating Se cap layers over the metallic films of step ii).

The base pressure of the sputtering chamber was about $10^{-6}$ mbar and the operating pressure was around 10−4 mbar. The metallic species were deposited on the substrates in the sequence of Cu/Sn/Zn/Cu to obtain the metallic stacks. Sputtering rate of each element was pre-determined through calibration runs and thickness measurements using a Veeco DEKTAK 150 surface profilometer. The total targeted thicknesses of the elemental films within the stack were 175, 165, and 230 nm for Cu, Zn, and Sn, respectively. Nearly 70% of the targeted Cu thickness was deposited over Mo, and the rest was placed over the Zn layer. The above-mentioned elemental metallic film thicknesses were targeted to yield compound layers with Cu-poor (Cu/Zn + Sn <1) and Zn-rich (Zn/Sn >1) compositions that are necessary for fabrication of efficient CZTSe type solar cells [7]. The metallic film thicknesses used were expected to yield about 1.4 μm thick compound layer based on the assumptions of 100% density and a compound density value of about 5.7 g/cm3. The practical thickness values are expected to be larger than 1.4 μm.

Annealing of the metallic stacks was performed in a tube furnace in a static 5%H2 + 95%Ar atmosphere at temperatures of 200, 250, 300, and 350 °C for 30 min. It should be noted that we selected milder annealing conditions compared to those employed by Gurav et al. [18] since their data indicated that a 60 minute anneal at temperatures at or above 300 °C caused appreciable Zn loss from the Cu-Zn-Sn films, which they compensated for by including excess Zn in their electroplated metallic layers. We did not include excess Zn in our stacks, but reduced the annealing time and also investigated the even lower annealing temperature of 200 °C in addition to higher temperatures.

The Se cap layers were deposited by thermal evaporation of Se (5 N) shots out of Mo boats. The base pressure of the evaporator was about 10−5 mbar and the operating pressure was around 10−4 mbar. Selenium thickness was monitored during the evaporation using an Inficon SQM 160 crystal controller/monitor. The targeted thickness of the Se layer was 1300 nm, which represented about 40% excess with respect to the amount that would be necessary to form the compound. This is because we determined, through calibration experiments, that excess Se was needed in the precursor layers to avoid formation of compounds with appreciable Se deficiency and associated secondary phases after the reaction step.

After the Se evaporation step, the (Cu-Zn-Sn)/Se precursor layers were reacted for 15 min in a tube furnace in a static 5%H2 + 95%Ar atmosphere at 550 °C. For simulating a rapid thermal process, the tube furnace with the process gas was first heated to the reaction temperature and the samples were then rapidly pushed into the hot zone [11]. The estimated ramping rate of the temperature in these experiments was about 5 °C/s. An effort to create an overpressure of Sn in the reaction environment we added Sn(II)Se powder with 4 N purity to the area around the samples on the sample holder.

In this manuscript the metallic stack samples are identified as CZT-AD, CZT-200, CZT-250, CZT-300 and CZT-350, and the compound layers obtained after the reaction step are marked as CZTSe-AD, CZTSe-200, CZTSe-250, CZTSe-300, and CZTSe-350. The ‘AD’ abbreviation refers to ‘as-deposited’ and the numerical values indicate the annealing temperatures for the metallic stacks. For example, CZT-350 implies a Cu/Sn/Zn/Cu metallic stack annealed at 350 °C for 30 min before the Se cap deposition and CZTSe-350 refers to the compound layer obtained by reacting the CZT-350/Se precursor structure at 550 °C for 15 min. It should be noted that the samples mentioned above were all produced from the same precursor structure (i.e. the sputtering and the Se evaporation steps were carried out during the same runs for all samples), only the metal stack annealing temperature being different. Since the CZTSe thin films were grown on conductive and non-transparent substrates, optical transmission and the electrical measurement in the plane of the films could only be performed after they were transferred from their substrates onto glass slides by transparent epoxy peeling approach as previously utilized by Basol [19]. The detailed experimental procedures used for mechanical transfer of the reacted films onto glass were described in our recent publication [11]. The crystalline structure and the structural quality of the films were determined by XRD measurements using a Rigaku Smartlab diffractometer with a CuKα radiation source ($\lambda = 1.5405 \text{ Å}$) at room temperature. The phase compositions were also determined by Raman scattering measurements (Princeton Instruments, Acton SP2750 0.750 mm Imaging Triple Grating Monochrometer) excited with a laser at a wavelength of 488 nm. The morphological and compositional analyses were performed by a Jeol JSM 6610 scanning electron microscope (SEM) and an Oxford Instruments Inca X-ray dispersive X-ray spectroscopy (EDX) system. The optical transmittance spectra were obtained using a Dongwoo Optron spectrophotometer in the wavelength range of 1000–1800 nm. The electrical characterization was performed using Van der Pauw method at room temperature. Electrical contacts in the Van der Pauw samples were made by Ag paste dots of about 1 mm diameter. The four electrical contacts were placed at the four corners of the 1 cm × 1 cm square samples.

3. Results and discussion

3.1. EDX

Various atomic ratios in the as-deposited and annealed metallic stacks, determined by EDX at an incident beam voltage of 25 kV are listed in Table 1. As can be seen from this table the as-deposited metallic stack is Cu-poor (Cu/Zn + Sn <1) and Zn-rich (Zn/Sn >1) as targeted, and this composition is retained in all of the annealed samples even for the highest anneal temperature of 350 °C. The Cu/(Zn + Sn) ratios for all the films are also relatively unchanged within the experimental error. These results are very different from the previously published work by Gurav et al., who found a drastic change (from 0.71 to 1.38) in the Cu/(Zn + Sn) ratio of their electroplated Cu-Zn-Sn films upon soft-annealing at 350 °C for 60 min [18]. As the results in Table 1 demonstrate, our sputter deposited films annealed by rapid thermal method for 30 min retained their composition well. Possible factors contributing...
Table 2 gives the compositional information for the CZTSe layers obtained after the reaction step. As can be seen from this data, there is a trend of increasing Cu/(Zn + Sn) ratio upon reaction with Se. The Zn/Sn ratio, on the other hand shows a decrease by at most 0.19 for all samples, except for the CZTSe-250 sample, which appears to have retained its relatively Zn-rich composition. The small changes observed in the Zn/Sn ratios are indicative of some Zn loss from the compound layer during the selenization step. Although addition of Sn(II)Se in the reaction environment was to prevent Sn loss from the CZTSe structure, it may also have an impact on Zn-loss. Redinger et al. showed that Zn-loss can be observed with increasing of Se over pressure at high temperatures (>500 °C) [20]. It is not very clear why sample CZT-250 retained Zn more efficiently compared to the other samples during the reaction step. Differences between the annealed layers in terms of their phase content may have played a role in this as will be discussed later. Data in Table 2 also shows that all CZTSe layers have a Se/Metal ratio around 1. This is a necessary (but not sufficient) condition indicating that the selenization process has close to ideal conditions for obtaining CZTSe structure.

3.2. XRD

The XRD patterns obtained from the metallic stacks are presented in Fig. 1. Diffraction peak positions associated with elemental Sn (JCPDS 03-065-0296) and Cu (JCPDS 01-070-3038), and the binary metallic phases of Cu₅Sn₅ (JCPDS 03-065-2303), CuSn (JCPDS 03-065-3434), Cu₂Zn₈ (JCPDS 01-071-0397), Cu₃Zn₂ (JCPDS 25-0322), Cu₅Zn₈ (JCPDS 03-065-0296) and Cu (JCPDS 01-070-3038), and the binary metallic phases of Cu₆Sn₅ (JCPDS 03-065-2303) and CuSn (JCPDS 03-065-3434) are all marked on this figure along with the peak associated with Mo. It is interesting to note that the peak maxima is at higher angles for the CZTSe-350 sample (22.9°) compared to the CZTSe-250 sample (22.6°). This is a necessary (but not sufficient) condition indicating that the selenization process has close to ideal conditions for obtaining CZTSe structure.

Table 2
Atomic ratios in CZTSe thin films as determined by EDX analysis.

<table>
<thead>
<tr>
<th>Sample ID</th>
<th>Cu (%)</th>
<th>Zn (%)</th>
<th>Sn (%)</th>
<th>Se (%)</th>
<th>Cu/(Zn + Sn)</th>
<th>Zn/Sn</th>
<th>Se/metal</th>
</tr>
</thead>
<tbody>
<tr>
<td>CZTSe-AD</td>
<td>22.9</td>
<td>13.5</td>
<td>13.1</td>
<td>50.4</td>
<td>0.86</td>
<td>1.03</td>
<td>1.02</td>
</tr>
<tr>
<td>CZTSe-200</td>
<td>22.6</td>
<td>13.5</td>
<td>13.8</td>
<td>50.1</td>
<td>0.83</td>
<td>0.98</td>
<td>1.00</td>
</tr>
<tr>
<td>CZTSe-250</td>
<td>22.2</td>
<td>14.9</td>
<td>12.4</td>
<td>50.5</td>
<td>0.82</td>
<td>1.20</td>
<td>1.02</td>
</tr>
<tr>
<td>CZTSe-300</td>
<td>22.3</td>
<td>12.9</td>
<td>13.1</td>
<td>50.7</td>
<td>0.89</td>
<td>0.98</td>
<td>1.03</td>
</tr>
<tr>
<td>CZTSe-350</td>
<td>22.8</td>
<td>13.0</td>
<td>13.2</td>
<td>50.2</td>
<td>0.87</td>
<td>0.99</td>
<td>1.02</td>
</tr>
</tbody>
</table>

CZT-AD and CZT-200 samples and it shifts to lower angles for samples annealed at or above 250 °C. It appears that the metallic films are dominated by CuSn and Cu₅Zn₈ phases at low temperatures, as signified by a broad peak at ~43.12°, and the dominant phase shifts to Cu₅Sn₅ with a sharper peak around ~42.98° at the annealing temperature of 250 °C and higher. The broad peak at low temperature samples, without doubt, has contribution from the unreacted Cu phase also. These results in general support the findings of Wibowo et al. who observed the XRD peak around 43° shifting to lower angles as the samples were heated up from room temperature to a temperature of 470 °C [22]. Another observation from Fig. 1 is the formation of a distinct Cu₅Zn₈ phase upon annealing at temperatures at or above 250 °C. For the lower temperature samples this phase appears as a shoulder of the main peak signifying a series of compositions present. It is also noted that the small Cu₅Zn₈ peaks at around 35° and 37.9° present in the low temperature films convert into minor CuSn and Cu₅Zn₈ phases in summary, the data in Fig. 1 demonstrates a noticeable change in the phase content of metallic films when the anneal temperature is increased to 250 °C.

Fig. 2. XRD diffraction pattern of kesterite CZTSe thin films.
The XRD patterns of the CZTSe thin films, which were obtained after the CZT samples of Table 1 were reacted with Se, are displayed in Fig. 2. As can be observed from this data irrespective of the annealing temperature of the CZT samples, all five films show diffraction peaks at the expected positions of CZTSe 112 (2θ = 27.15°), 220/204 (2θ = 45.10°), and 312/116 (2θ = 53.45°) planes (JCPDS 01-070-8930). The estimated positions for the other lower intensity peaks of CZTSe with kesterite structure are also shown in the figure and they correlate well with the data. The Mo (JCPDS 01-089-5023) peak at 40.50° and the MoSe2 (JCPDS 09-0312) peaks at around 31.55° and 55.87° are due to the substrate. Presence of MoSe2 indicates reaction of the Mo layer with Se at 550 °C under the Se-rich conditions we provided during the reaction period. Moreover, additional peaks were observed for CZTSe-AD, CZTSe-200, CZTSe-300, and CZTSe-350 thin films, which may be attributed to SnSe (JCPDS 01-089-0236) and CuSe2 (JCPDS 00-018-0453) phases. A considerably minor peak was observed around at 48° in all patterns, which may be attributed to CuSe (JCPDS 01-072-8417) [23]. Apart from the MoSe2 and CuSe, which is highly conductive phase and has a detrimental effect on the cell performance, the CZTSe-250 sample yielded dominant characteristic diffraction peaks of CZTSe. Lack of secondary phases in this film correlates well with its desirable composition shown in Table 2.

Fig. 3 shows the full width at half maximum (FWHM) values obtained from the (112) peaks of Fig. 2. As can be seen from this figure the FWHM value goes down as the annealing temperature of the metallic films increases, reaching a minimum for the CZTSe-250 sample and then increases sharply for films annealed at higher temperatures. Decreasing FWHM can be correlated with improved crystallite size and lack of secondary phases that may contribute to the peak width. In that respect the CZTSe-250 sample appears to be the best quality film.

The increase observed in the FWHM value for the CZTSe-350 sample may not signify a deterioration of the crystallite size in the material but rather it may be due to secondary phases (such as ZnSe, which has a 111 peak at 2θ = 27.22°) that may broaden the 112 diffraction peak. Although all of the reacted films of Fig. 2 showed characteristic peaks of CZTSe, their purity cannot be fully determined from this data since ZnSe (JCPDS 01-071-5977) and Cu2SnSe3 (CTSe) (JCPDS 01-072-8034) phases share a similar diffraction pattern with kesterite CZTSe. Additional complementary measurements utilizing Raman spectroscopy is required to further study the phase content of these CZTSe layers.

Fig. 4 presents the Raman spectra data collected from our CZTSe samples. Once again, it can be seen from the data of Fig. 4 that irrespective of the annealing temperature of the metallic stacks, the spectra of the reacted layers are dominated by two peaks located around at 196 cm⁻¹ and 173 cm⁻¹. Both of these intense peaks are attributed to kesterite CZTSe phase.

The lower intensity characteristic peak at around 232–233 cm⁻¹ also belongs to CZTSe [6]. A minor peak detected at 242–245 cm⁻¹ can be attributed to MoSe2 phase, which was also observed in the XRD pattern of Fig. 2. Unlike the other films, CZTSe-300 sample displayed a minor peak around at 250 cm⁻¹ and 252 cm⁻¹ which may be due to trace amounts of ZnSe and Cu2SnS3 phases, which could not be distinguished by XRD [24–26]. The spectra of CZTSe-350 sample also show the presence of the CuSe2 phase in support of the XRD data. This peak is not clearly seen for CZTSe-300 sample (which has the Cu-selenide phase according to the XRD data) due to the interference from other secondary phase peaks.

3.4. SEM

The SEM images taken from the surface and cross-section of the metallic precursor layers are given in Fig. 5. As can be seen from these SEMs although the metallic films were subjected to an annealing treatment step at various temperatures, the treatments did not change the morphology of the films much except that some fusion between the globules can be seen in the cross-section of sample CZT-350. This is because our annealing temperatures were below the melting temperature of Zn and the low melting Sn was sandwiched between two solid films of Cu/Cu-Sn alloys and Cu-Zn alloys during deposition.

Fig. 6 shows the top and cross-sectional view SEM images of the CZTSe layers. Irrespective of the annealing process before the reaction step, all of the films display non-uniform polycrystalline surface structures. The thickness values appear to be in the 1.4–2 μm range considering the fact that the cross sectional views are at 45° angle. CZTSe-AD thin film contains many voids that are visible in the surface SEM. Increasing the annealing temperature to 250 °C reduces the density of these voids giving rise to a more dense structure. Raising the annealing temperature above 250 °C causes appreciable change in the morphology of the reacted films. CZTSe-300 and CZTSe-350 samples display a rougher morphology with larger particle size and better fusion between the
Fig. 5. Top and cross-sectional view SEMs of the metallic films: CZT-AD (a, f), CZT-200 (b, g), CZT-250 (c, h), CZT-300 (d, i), and CZT-350 (e, j).
Fig. 6. Top and cross-sectional view SEMs of the reacted films; CZTSe-AD (a, f), CZTSe-200 (b, g), CZTSe-250 (c, h), CZTSe-300 (d, i), and CZTSe-350 (e, j) kesterite films.
content of the CZTSe layers were found to be lower except for the one obtained from the metallic film that was annealed at 250 °C. This CZTSe layer was also found to be the best in terms of its crystalline quality and purity, containing substantially just the kesterite CZTSe phase, other than a very small amount of CuSe. Other CZTSe layers were found to contain trace amounts of secondary phases such as SnSe, CuSe2, ZnSe and Cu2SnSe3. SEM micrographs showed denser structure for CZTSe layers grown employing metallic films annealed at or above 250 °C. Optical band gap, resistivity and carrier concentration of the best quality film were found to be about 0.87 eV, 2 Ω-cm and 4 × 10^{17} cm^{-3}, respectively.

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[10] M.A. Olgar, Y. Atasoy, B. Baçoğlu, M. Danilson, M. Grossberg, J. Krustok, E. Mellikov, Cu2ZnSnSe4 (CZTSe) thin films grown by a two-stage process included the steps of sputter deposition of a Cu/Zn/Cu metallic stack, annealing the stack at temperatures of 200–300 °C for 30 min, evaporation of a Se cap over the metallic stack thus forming a precursor layer, and subjecting the precursor layer to a reaction step at 550 °C for 15 min. Influence of the metallic stack annealing process on the properties of the CZTSe layers obtained after the reaction step was studied through XRD, EDX, SEM and Raman spectroscopy measurements. The results showed that heat treatment of the metallic stacks did not cause much change in their morphology and the Cu-poor Zn-rich compositions, however their phase content changed noticeably when the anneal temperature was raised to 250 °C. After reaction with Se, the Zn

surface features. This is expected since these films contain Cu-Se phase(s), which can act as low-melting fusing agents during the high temperature formation of the compound layer.

3.5. Optical and electrical properties

The optical band gap values for CZTSe films reported in the literature vary broadly (0.8–1.6 eV) and this variation has been attributed to the presence of appreciable amount of secondary phases (such as SnSe and Cu2SnSe3) in some of the layers used in the bandgap measurements [27]. The optical band gap of the CZTSe-250 layer, which was our best quality film based on the characterization presented above, was determined from the (αhv)^2 vs (hv) curves (from the transmission measurements) using Eq. (1) [4];

\[
\alpha h\nu = A(h\nu-E_0)^{1/2}
\]

where α is the optical absorption coefficient, A is a constant, and E_0 is the optical band gap. As shown in Fig. 7, the optical band gap value obtained by extrapolating the (αhv)^2 vs (hv) plot to the horizontal photon energy axis is about 0.87 eV.

The resistivity of the CZTSe-250 layer was measured using a square shaped Van der Pauw pattern with contacts at the four corners. The film had p-type conductivity and its resistivity and carrier concentration values were measured to be around 2 Ω-cm and 4 × 10^{17} cm^{-3}, respectively.

4. Conclusions

Cu2ZnSnSe4 (CZTSe) thin films grown by a two-stage process were characterized in terms of their structural, optical and electrical properties. The film growth approach included the steps of sputter depositing a Cu/Zn/Cu metallic stack, annealing the stack at temperatures of 200–300 °C for 30 min, evaporation of a Se cap over the metallic stack thus forming a precursor layer, and subjecting the precursor layer to a reaction step at 550 °C for 15 min. Influence of the metallic stack annealing process on the properties of the CZTSe layers obtained after the reaction step was studied through XRD, EDX, SEM and Raman spectroscopy measurements. The results showed that heat treatment of the metallic stacks did not cause much change in their morphology and the Cu-poor Zn-rich compositions, however their phase content changed noticeably when the anneal temperature was raised to 250 °C. After reaction with Se, the Zn


